



AF#  
JFW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Appl. No.	10/003,908	Confirmation No.	7739
First Inventor	William R. Entley	Filing Date	11/1/2001
Tech. Center/ Art Unit	1765	Examiner	Anita Karen Alanko
Title:	In Situ Plasma Process To Remove Fluorine Residues From The Interior Surfaces Of A CVD Reactor		
Docket No.:	NVS013 US	Customer No.:	34036

Santa Clara, California  
October 19, 2004

MAIL STOP AF  
COMMISSIONER FOR PATENTS  
P.O. Box 1450  
Alexandria, VA 22313-1450

**AMENDMENT AFTER FINAL ACTION**

Dear Sir:

In response to the Advisory Action dated August 25, 2004, please amend the above-identified application as follows.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 6 of this paper.